

### AMENDMENTS TO THE CLAIMS

1. (Canceled)

2. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; ~~wherein the correcting further comprises:~~

monitoring a condition within the processing system by sensing a change in state of a portion of the processing system through which the robot must extend to reach the exchange position;

determining the a shift in the exchange position based on the monitored condition;  
and

correcting motion of the robot to compensate for the shift in the exchange position.

3. (Currently Amended) The method of claim 2, wherein the ~~monitoring further comprises:~~

~~—sensing a change in temperature within [[a]] the portion of the processing system~~  
change in state is an instruction by a controller to change the state of the at least one processing chamber.

4. (Previously Presented) The method of claim 2, wherein the ~~monitoring further comprises:~~

~~—sensing a change in state of the at least one processing chamber~~  
change in state is a change in the state of the transfer chamber.

5. (Previously Presented) The method of claim 2, wherein the ~~monitoring state further comprises:~~

~~\_\_\_\_\_sensing a change in state of at least two processing chambers~~ change in state is an instruction by a controller to change the temperature of the at least one processing chamber.

6. (Currently Amended) The method of claim 2, wherein the ~~monitoring further comprises:~~

~~\_\_\_\_\_sensing a change in state of a second processing chamber different than a first processing chamber having the exchange position defined therein~~ change in state is a shift in a centerline of the one or more process chambers with respect to a centerline of the transfer chamber.

7-9. (Canceled)

10. (Currently Amended) ~~A~~ The method of claim 3 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

monitoring a condition within the processing system by sensing a change in temperature within, ~~wherein the portion of the processing system is a facet of the transfer chamber through which the robot must extend to reach the exchange position;~~

determining a shift in the exchange position based on the monitored condition; and  
correcting motion of the robot to compensate for the shift in the exchange position.

11. (Previously Presented) The method of claim 10, wherein the sensing the change in temperature further comprises:

sensing a change in temperature of a different facet of the transfer chamber.

12. (Currently Amended) A The method of claim 2 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system;

monitoring a condition within the processing system;

determining a shift in the exchange position based on the monitored condition by,  
~~wherein the determining further comprises:~~ sensing a change in position of the at least one  
processing chamber; and

correcting motion of the robot to compensate for the shift in the exchange position.

13. (Currently Amended) The method of claim 12, wherein the sensing the change in position of the at least one processing chamber further comprises:

sensing a metric indicative of a position of a centerline of the at least one processing chamber.

14. (Currently Amended) The method of claim 12, wherein the sensing the change in position of the at least one processing chamber further comprises:

sensing a metric indicative of a position of a centerline of the transfer chamber.

15. (Previously Presented) The method of claim 2, wherein the determining further comprises:

resolving a change in the exchange position based on empirical data.

16. (Original) The method of claim 15, wherein the empirical data is representative of a change in at least one of position and orientation of the processing chamber relative to the transfer chamber due to thermal effects.

17. (Previously Presented) The method of claim 2, wherein the determining further comprises:

resolving a change in the exchange position based on modeled data.

18. (Original) The method of claim 17, wherein the modeled data is representative of a change in at least one of position and orientation of the processing chamber relative to the transfer chamber due to thermal effects.

19. (Previously Presented) The method of claim 2, wherein the monitoring the condition further comprises:

tracking time between state changes of at least one processing chamber.

20. (Previously Presented) The method of claim 2, wherein the determining further comprises:

accounting for rates of thermal expansion.

21. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

correcting motion of the robot to compensate for a shift in the exchange position by[,] wherein the correcting further comprises:

measuring a change in at least one of the position and orientation of the at least one processing chamber relative to the transfer chamber; and

adjusting motion of the robot to compensate for the detected measured changes.

22. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

correcting motion of the robot to compensate for a shift in the exchange position by;  
~~wherein the correcting further comprises:~~

sensing a change in at least one of the position and orientation of the at least one processing chamber relative to the transfer chamber; and

adjusting motion of the robot to compensate for the sensed changes.

23. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

correcting motion of the robot to compensate for a shift in the exchange position by[.]]~~wherein the correcting further comprises:~~

resolving a change in at least one of the position and orientation of the at least one processing chamber relative to the transfer chamber; and

adjusting motion of the robot to compensate for the detected resolved changes.

24. (Currently Amended) The method of claim 23, wherein the resolving changes further comprises at least one of modeling thermal expansion of the transfer chamber, modeling thermal expansion of the at least one processing chamber, and utilizing empirical data that is representative of relative positions of the at least one processing chamber relative to the transfer chamber due to thermal effects.

25. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

correcting motion of the robot to compensate for a shift in the exchange position,  
~~wherein the shift in the exchange position is due to a change in the thermal profile of the~~  
transfer chamber.

26. (Currently Amended) A The method of claim 1 for transferring a substrate in a processing system having at least one processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the processing system; and

correcting motion of the robot to compensate for a shift in the exchange position,  
~~wherein the shift in the exchange position is due to a change in the thermal profile of the~~  
at least one processing chamber.

27. (Currently Amended) A method for transferring a substrate in a processing system having at least a first processing chamber coupled to a transfer chamber housing a robot, the method comprising:

defining an exchange position of the first processing chamber;

sensing temperature of at least one component of the system that results in a shift in the exchange position;

resolving the shift in the exchange position corresponding to the sensed temperature; and

correcting robot motion to compensate for the shift in the exchange position.

28. (Previously Presented) The method of claim 27, wherein the sensing further comprises:

sensing a temperature of at least one facet of the transfer chamber.

29. (Previously Presented) The method of claim 27, wherein the resolving further comprises:

determining a change in at least one of the position and orientation of a facet of the transfer chamber from which the temperature was sensed.

30-34. (Canceled)

35. (Currently Amended) A The method of claim 30 for transferring a substrate in a processing system having at least a first processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the first processing chamber relative to a predefined reference point within the transfer chamber;

detecting a shift in the exchange position by, wherein the detecting further comprises: determining a change in at least one of the position and orientation of a facet of the transfer chamber corresponding to a change in a sensed temperature; and

correcting the taught robot motion to compensate for the shift in the exchange position.

36. (Canceled)

37. (Currently Amended) A The method of claim 30 for transferring a substrate in a processing system having at least a first processing chamber coupled to a transfer chamber housing a robot, the method comprising:

teaching the robot to move to an exchange position defined in the first processing chamber relative to a predefined reference point within the transfer chamber;

detecting a shift in the exchange position by, wherein the detecting further comprises: determining a change in at least one of position and orientation of the first processing chamber; and

correcting the taught robot motion to compensate for the shift in the exchange position.

38-39. (Canceled)

40. (Currently Amended) A method for transferring a substrate in a processing system having at least a first processing chamber coupled to a transfer chamber housing a robot, the method comprising:

establishing a predefined reference point within the transfer chamber and an exchange position of the first processing chamber;

teaching [[a]] the robot to move to the exchange position;

monitoring relative positional change between the reference point and exchange position, wherein the monitoring the relative positional change between the reference point and exchange position further comprises detecting a change in lateral position of a substrate support disposed in the first processing chamber; and

correcting the taught position of the robot in response to the relative positional change, thereby allowing the robot to arrive at the exchange position.

41. (Currently Amended) A method for transferring a substrate in a processing system having at least a first processing chamber coupled to a transfer chamber housing a robot, the method comprising:

establishing a predefined reference point within the transfer chamber and an exchange position of the first processing chamber;

teaching [[a]] the robot to move to the exchange position;

monitoring relative positional change between the reference point and the exchange position, wherein the monitoring the relative positional change between the reference point



and the exchange position further comprises detecting a change in lateral position of the reference point of the transfer chamber due to thermal changes of the transfer chamber; and

correcting the taught position of the robot in response to the relative positional change, thereby allowing the robot to arrive at the exchange position.

42. (Currently Amended) A substrate processing system comprising:

a transfer chamber;

a processing chamber coupled to the transfer chamber;

a robot disposed in the transfer chamber and adapted to transfer substrates between the transfer chamber and the processing chamber;

at least one sensor adapted to provide a temperature metric from which a change in position between the transfer chamber and the processing chamber may be resolved; and

a controller coupled to the robot and adapted to provide instructions for correcting the robot's motions in response to the metric provided by the at least one sensor.

43. (Previously Presented) The substrate processing system of claim 42, wherein the at least one sensor provides temperature information of the transfer chamber.

44. (Previously Presented) The substrate processing system of claim 42, wherein the at least one sensor further comprises a plurality of temperature sensors providing metrics indicative of a temperature profile of the transfer chamber.

45. (Previously Presented) The substrate processing system of claim 42, wherein the at least one sensor provides temperature information of the processing chamber.

46. (Canceled)